

01/10

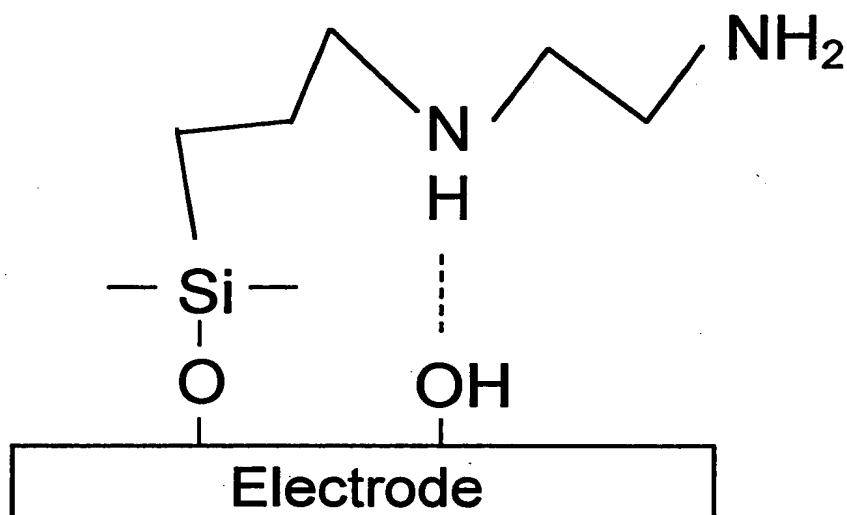


Fig. 1

Electrode stock

Ar plasma, 5 min
250 mTorr, 250W

OH OH

Electrode

AEAPS vapor deposition
5 min, RT, 2hr cure @ 90°C

NH₂ NH₂

Electrode

Permlayer deposition + Schiff base formation

Permeation layer

Electrode

Schiff base reduction with NaBH₃CN

Permeation layer

Electrode

Permeation layer

Electrode

HN NH NH NH NH NH

Si-O-Si-O-Si-O-Si-O

Electrode

Fig. 2

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Fig. 3A



Fig. 3B

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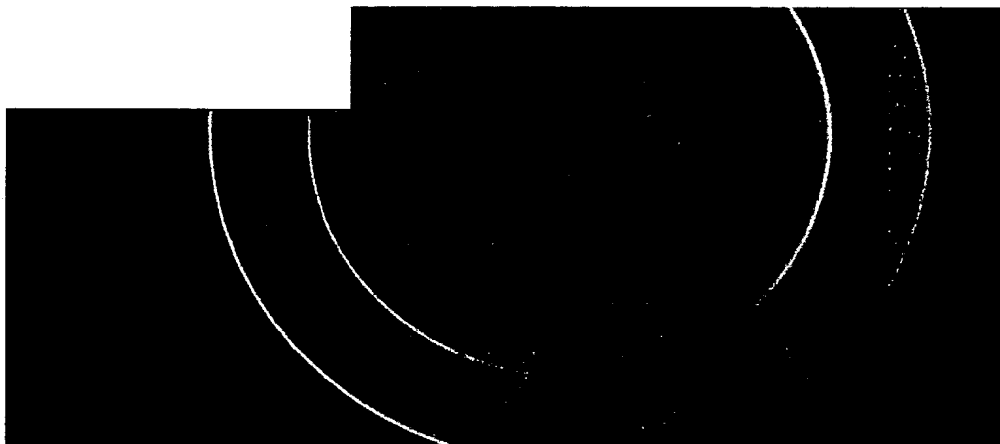


Fig. 4A

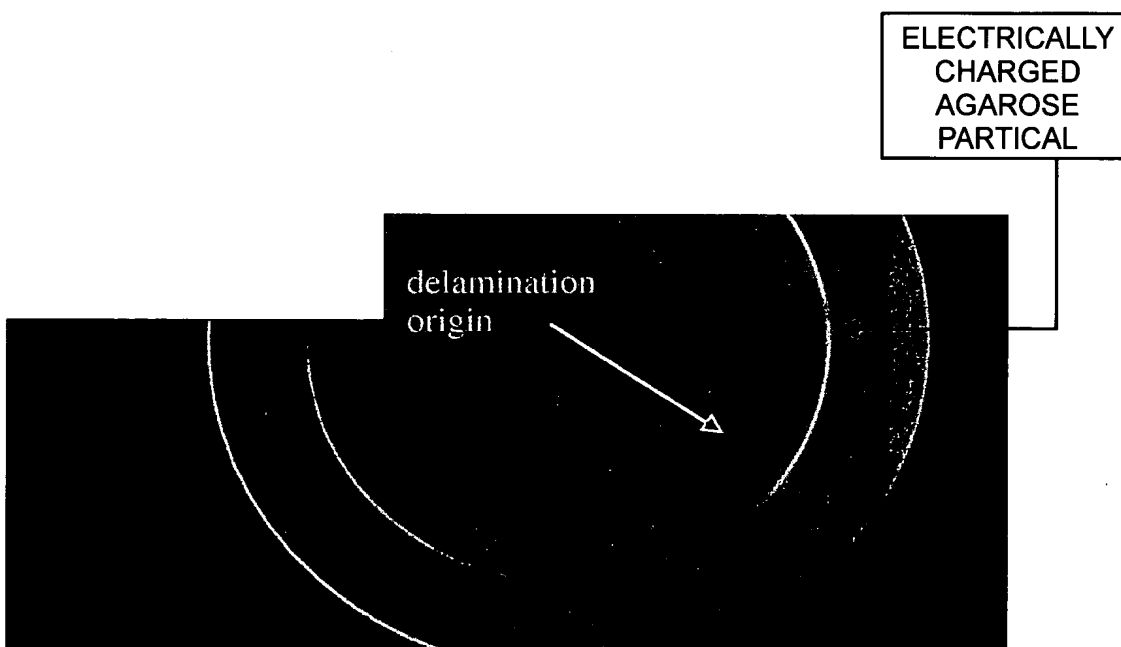


Fig. 4B

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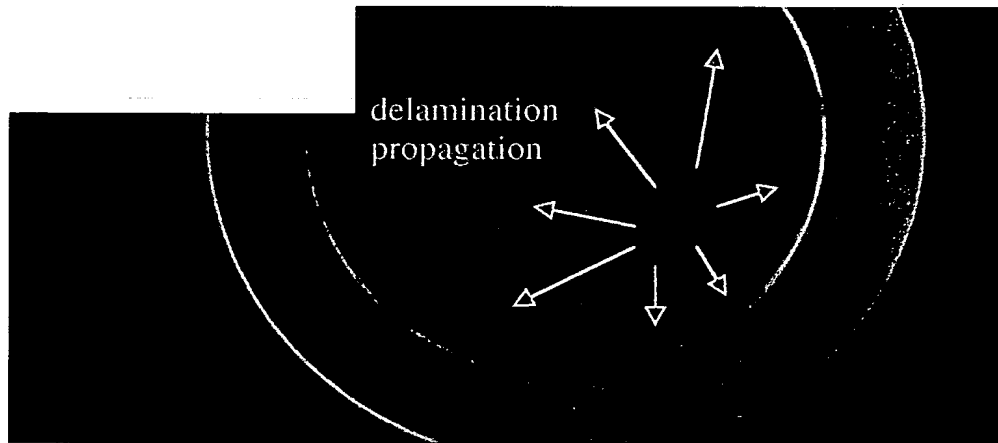


Fig. 4C

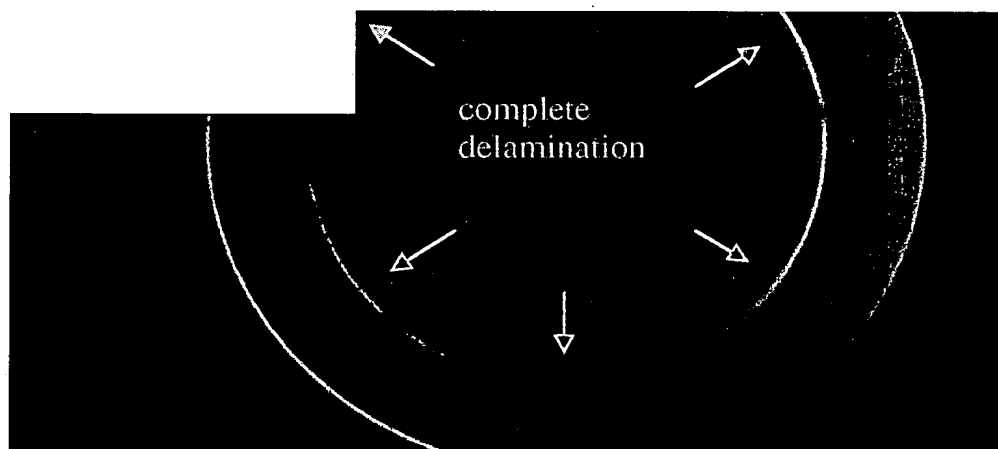


Fig. 4D

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Fig. 5A



Fig. 5B

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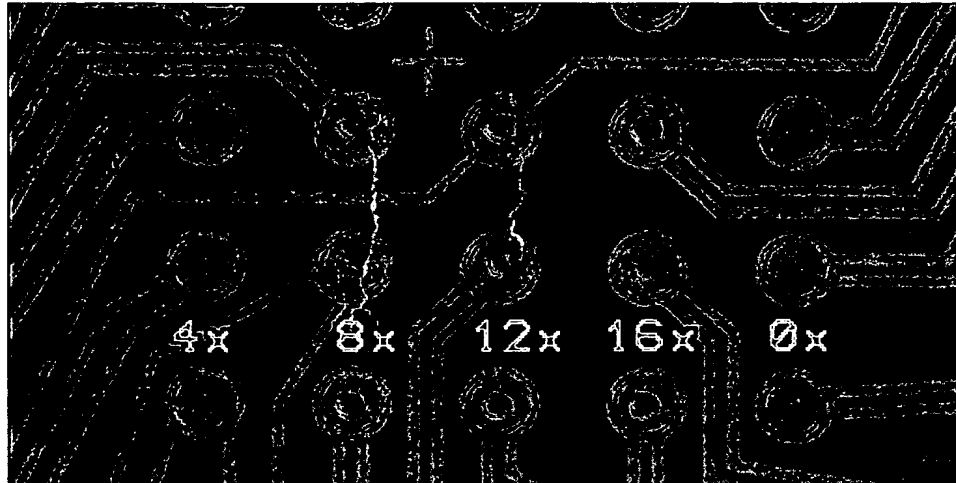


Fig. 6A

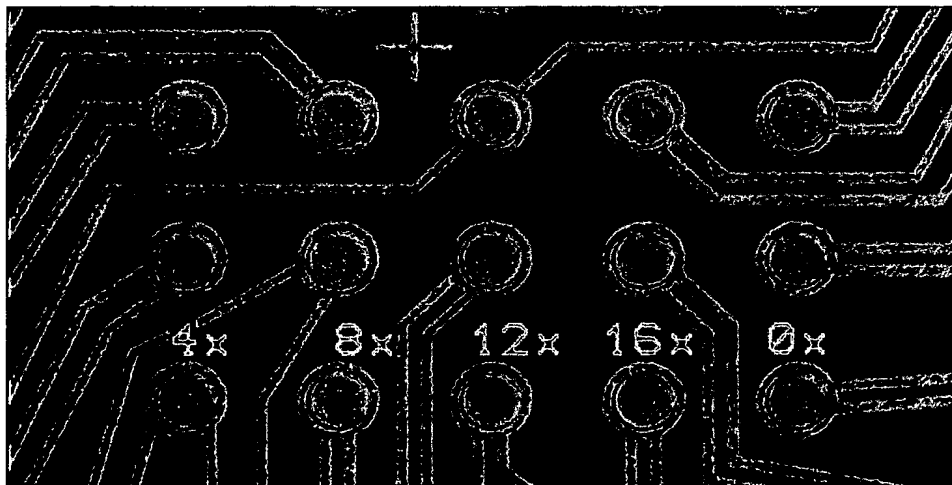


Fig. 6B

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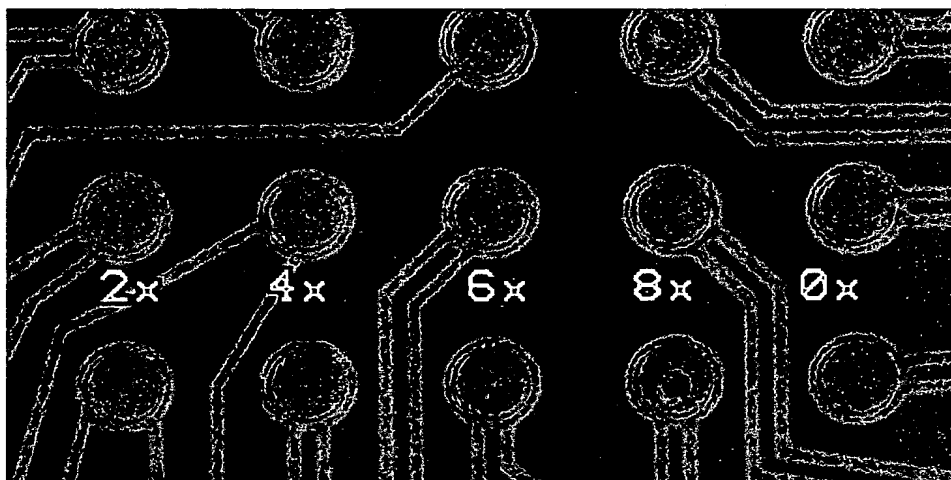


Fig. 7A

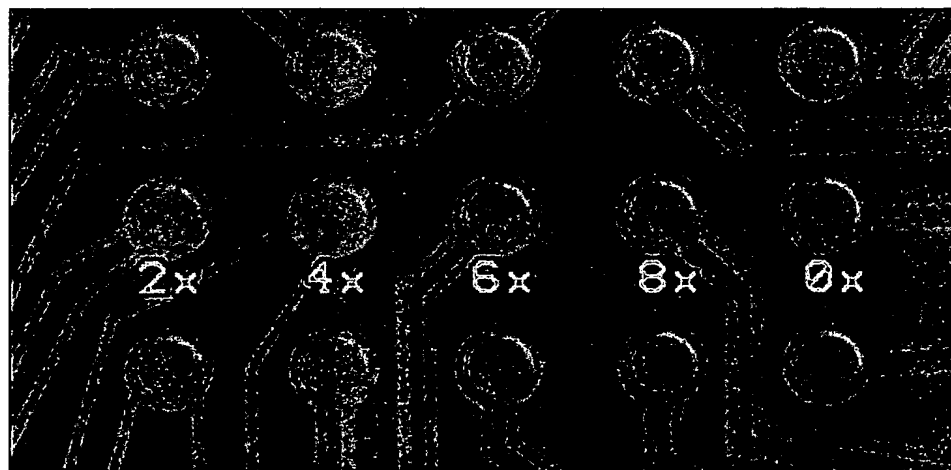


Fig. 7B

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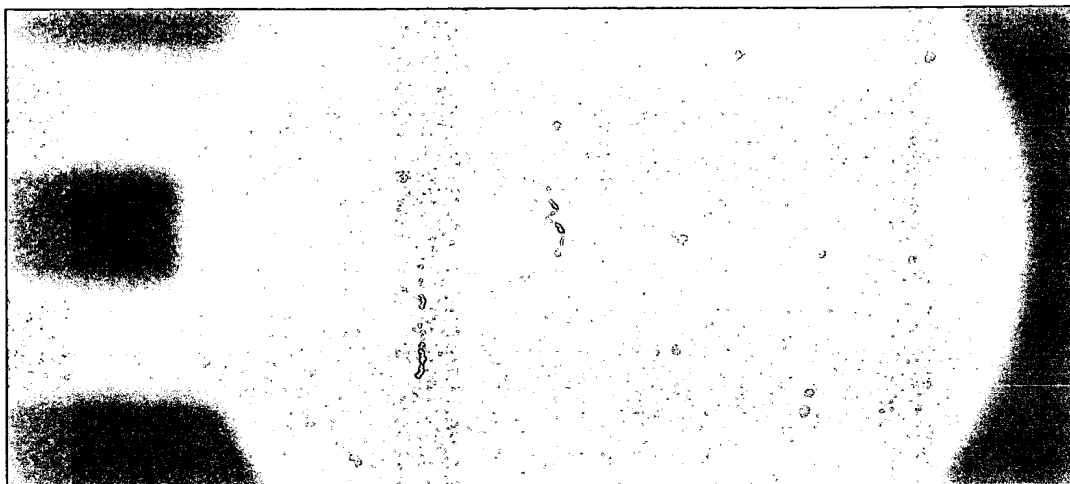


Fig. 8

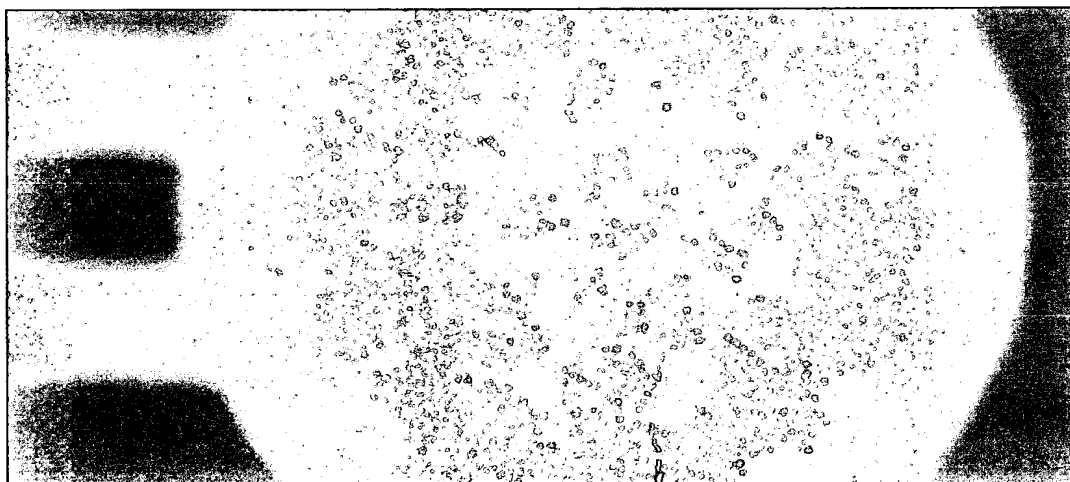


Fig. 9

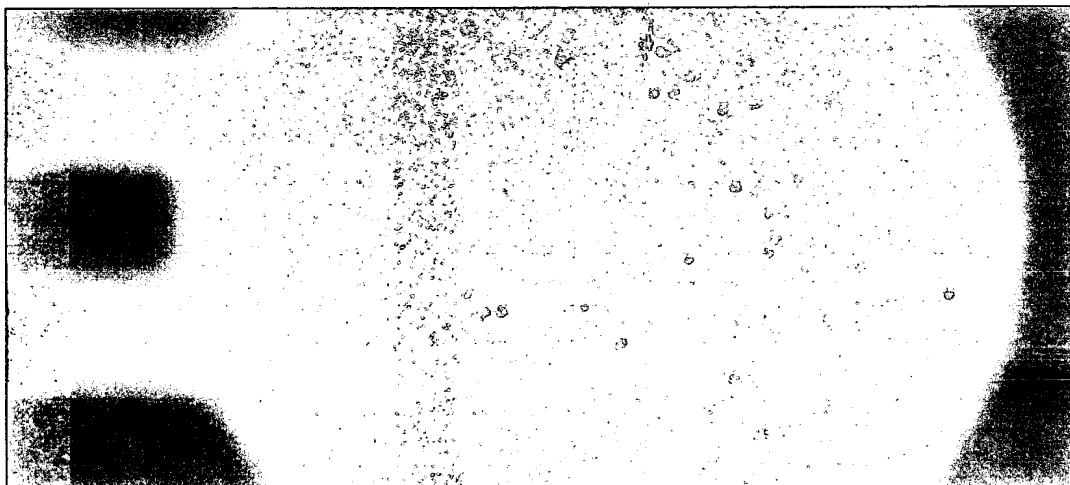


Fig. 10

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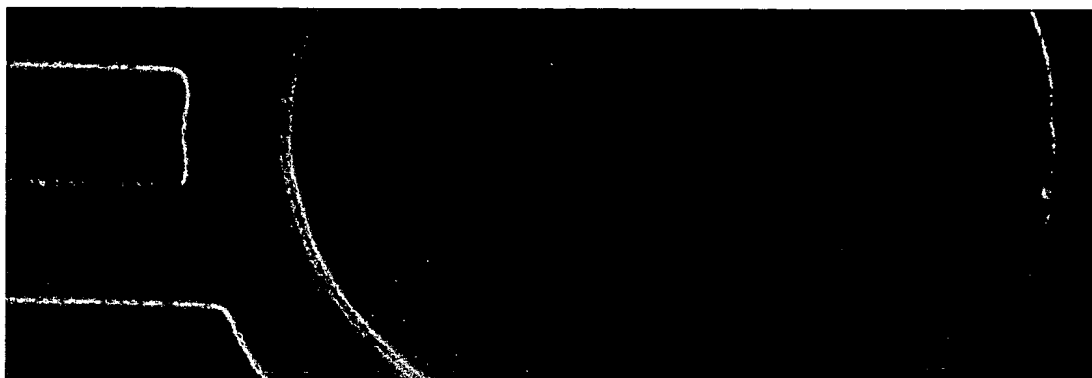


Fig. 11



Fig. 12



Fig. 13